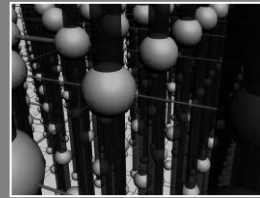
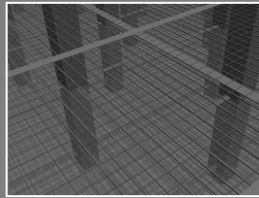
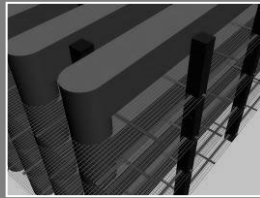


Fast and Accurate Full-chip Extraction and Optimization of TSV-to-Wire Coupling

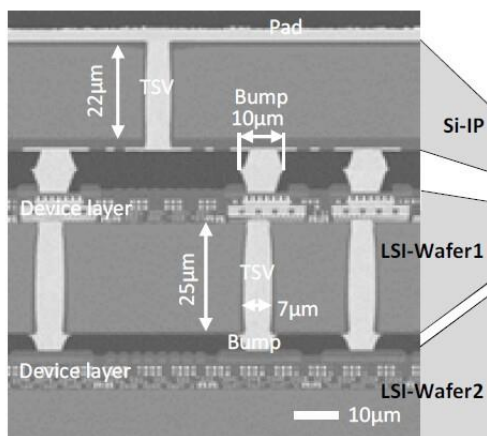


Yarui Peng¹, Dusan Petranovic² and Sung Kyu Lim¹

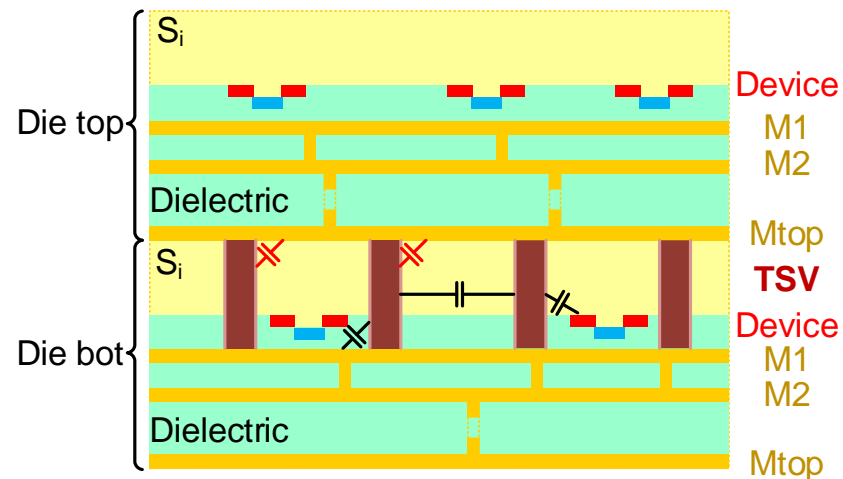
¹Georgia Institute of Technology, Atlanta, GA

²Mentor Graphics, Fremont, CA

- 3D IC: a solution to alleviate interconnect delay and power
- **New parasitics** exist in 3D IC
 - TSV-to-TSV, TSV-to-wire coupling, μ bump parasitics etc.
 - Need 3D interconnection extraction tool for TSV-to-wire coupling
 - Affect performance, power, noise[1]



SEM of a via-last die-stacking technology[2]



TSV related coupling elements

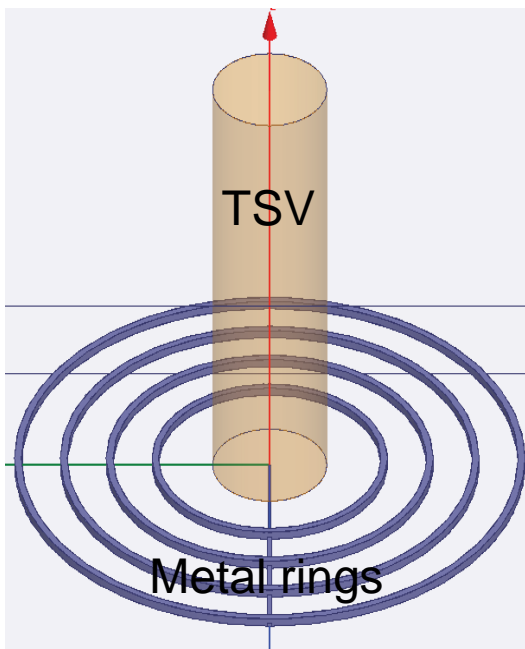
[1] C. Liu et al., "Full-chip TSV-to-TSV coupling analysis and optimization in 3D IC," DAC11

[2] Aoki, M. et al, "Fabricating 3D integrated CMOS devices by using wafer stacking and via-last TSV technologies, IEDM13

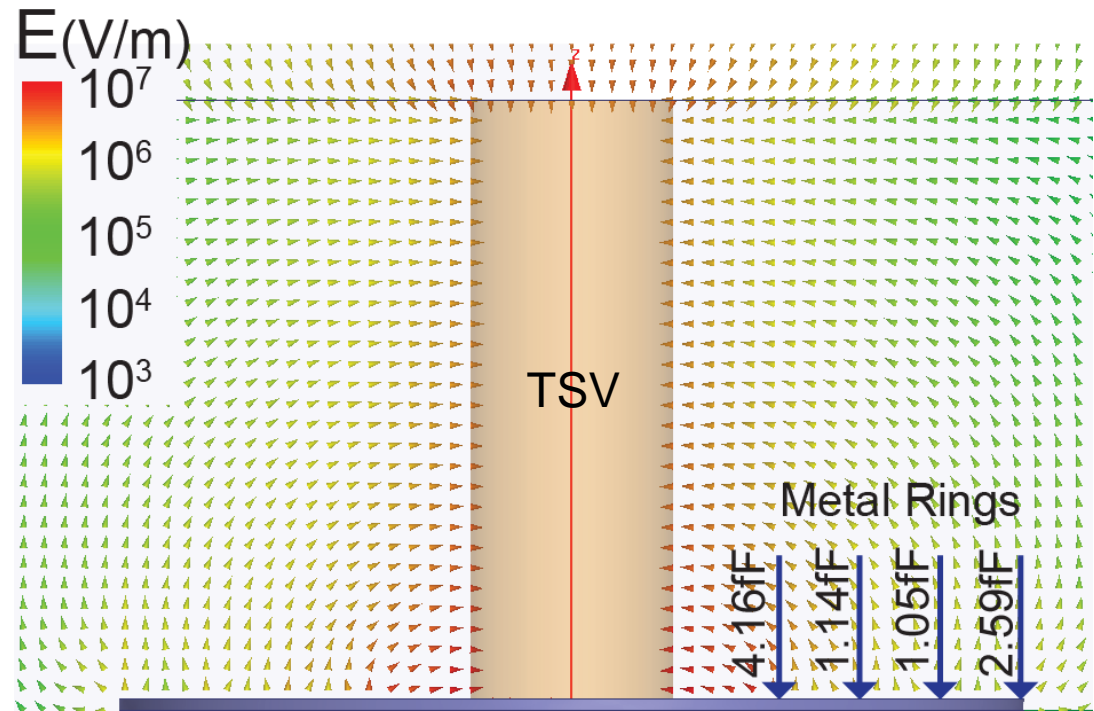
Multiple Wire Effect

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- A TSV structure with 4 wire rings are simulated in HFSS
- Much smaller coupling cap to TSV on Middle rings



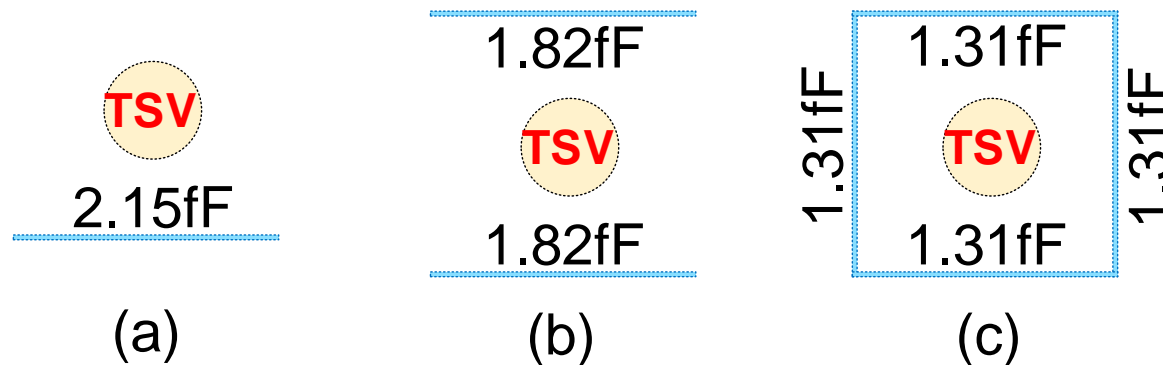
TSV-ring structure



E-field distribution and extracted capacitance

Wire Coverage Effect

- **More wire covering leads to heavier E-field sharing around TSV**
 - Reduces the coupling capacitance per each wire surrounding TSV
 - The total coupling capacitance to TSV still increases

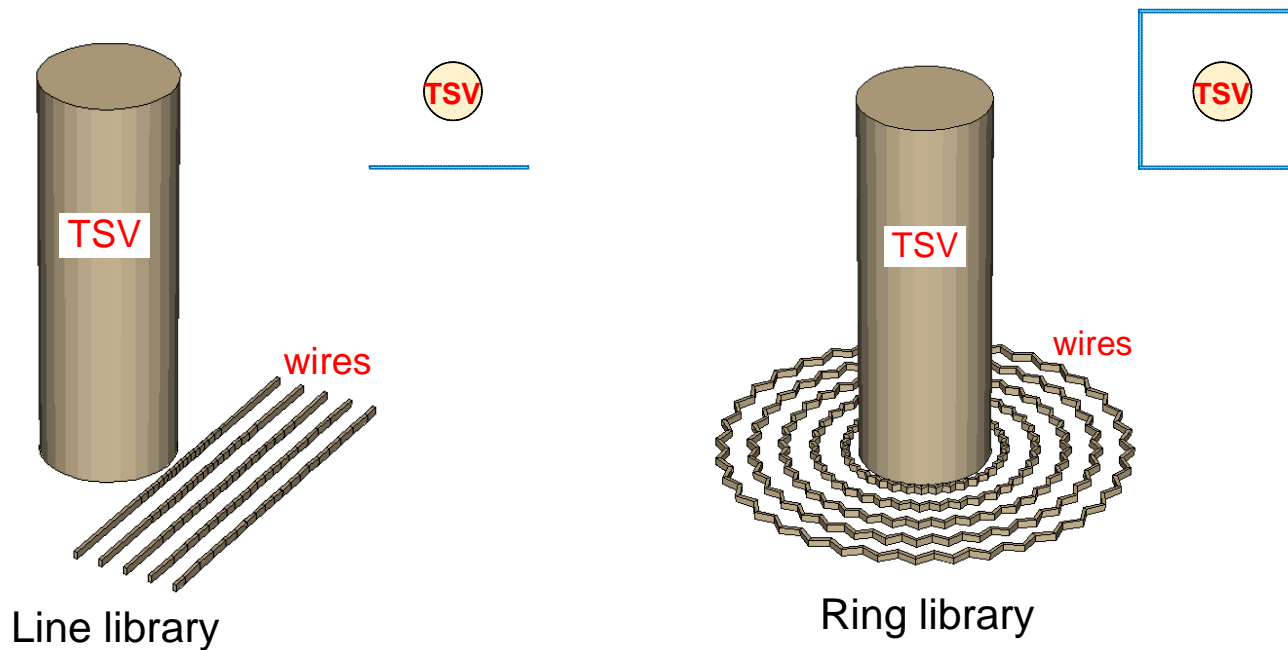


Three case studies of wire coverage effect

TSV-to-wire Libraries Generation

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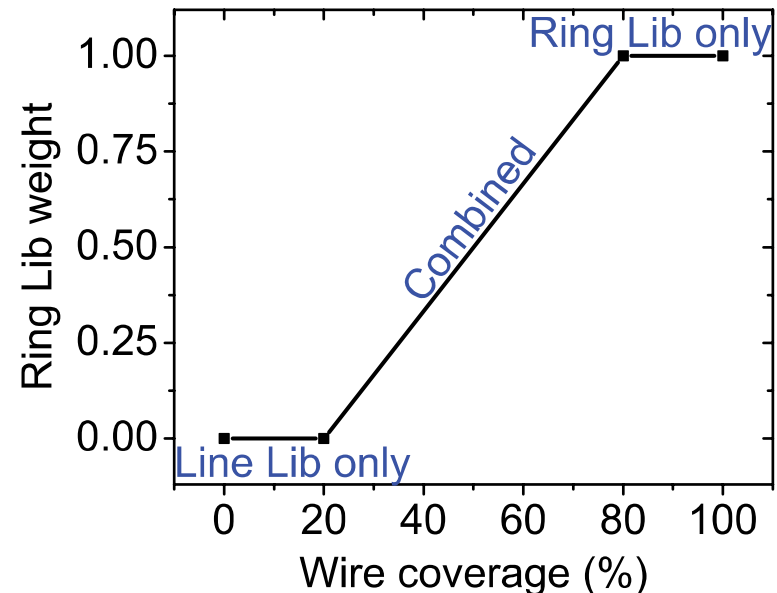
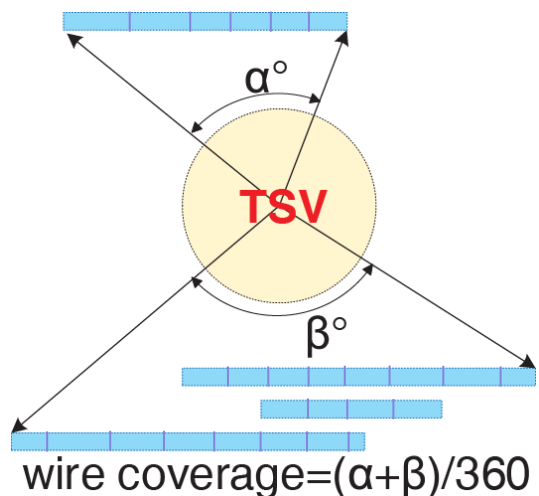
- **Two libraries are built to handle E-field sharing effects:**
 - **Line library:** used for cases when wire coverage is low
 - **Ring library:** used for cases when wire coverage is high



Pattern Matching Algorithm

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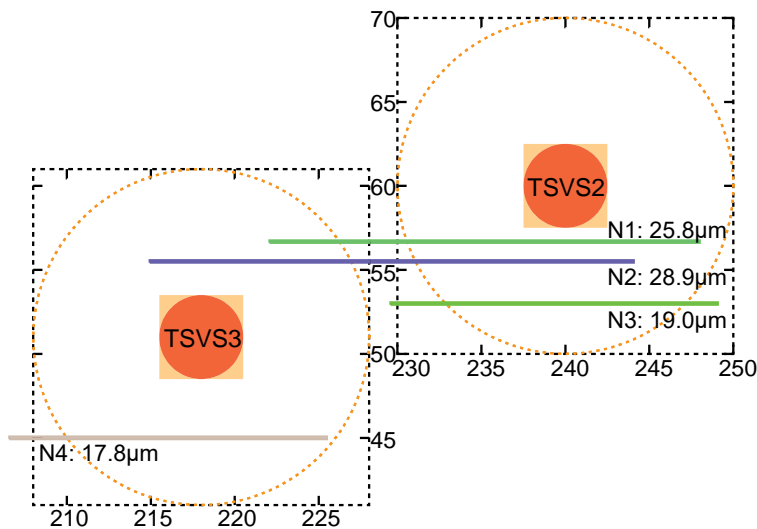
- Extract TSV-to-wire capacitance on the nearest metal layers
- Divide wire into segments
 - finer grid sizes are given to near-TSV region
- Segment capacitances extraction based on wire coverage and neighbor segments



Validation with Sample Layout

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- We validate the extraction result against Synopsys Raphael on a sample layout from a 3D design

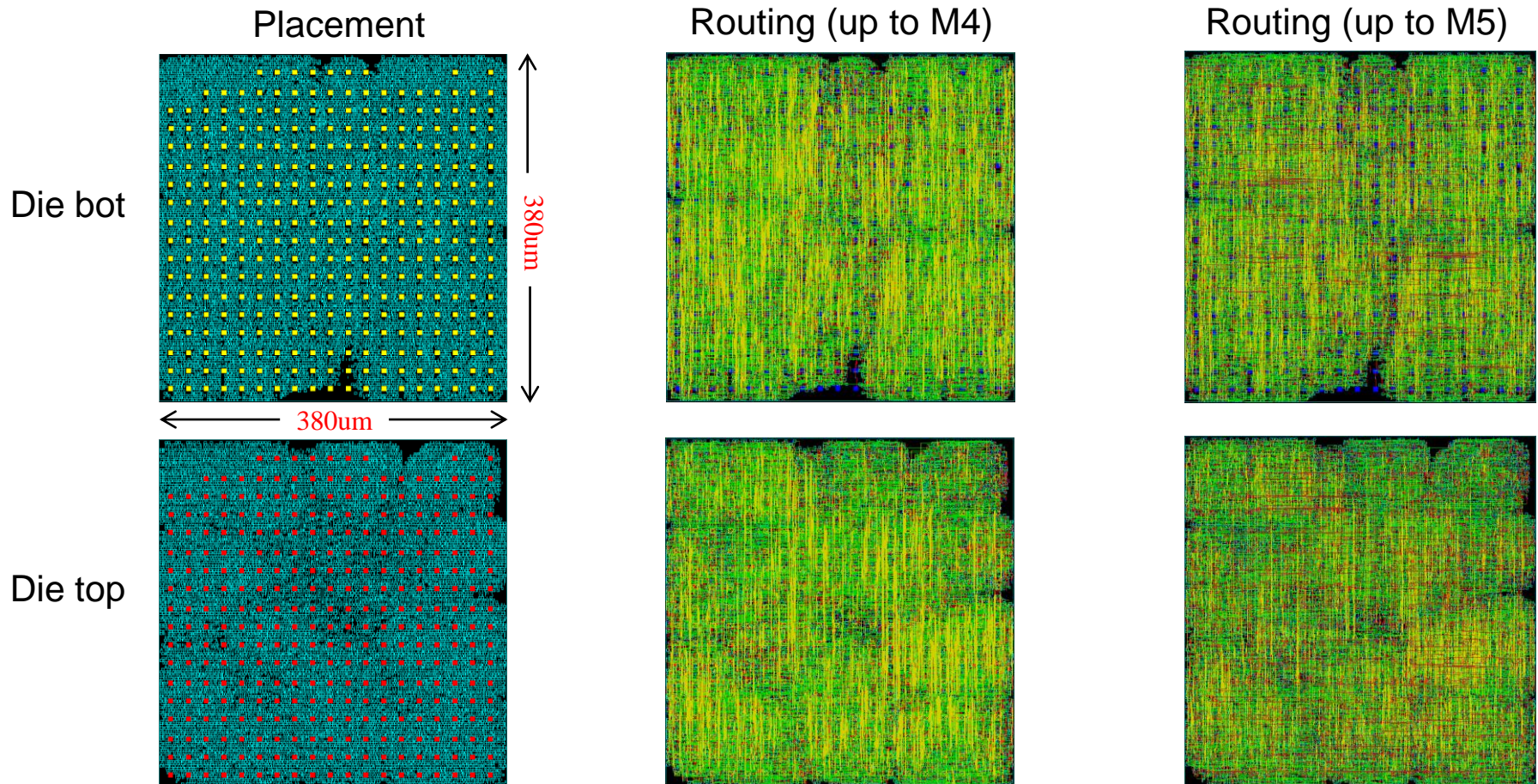


Sample Layout

TSV	Wire	Raphael	Our method		
			Ring lib	Combined	Line lib
S2	N1	1.76	1.49	1.93	2.07
S2	N2	0.76	0.68	0.76	0.78
S2	N3	0.81	0.86	0.81	0.79
S3	N1	0.31	0.29	0.31	0.34
S3	N2	1.38	1.28	1.33	1.37
S3	N4	1.62	1.49	1.53	1.57

Extraction results

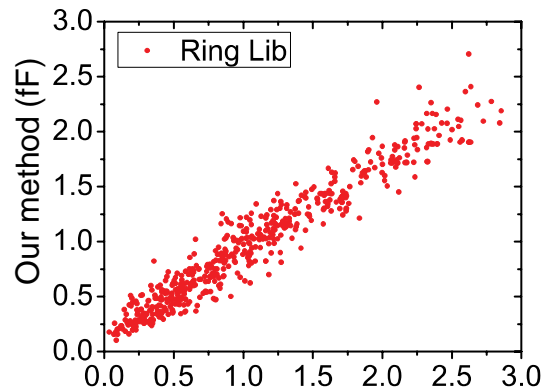
- 64-point FFT, 47K gates
- 330 TSVs: 2 μ m radius, 5 μ m landing pad width, 0.5 μ m KOZ



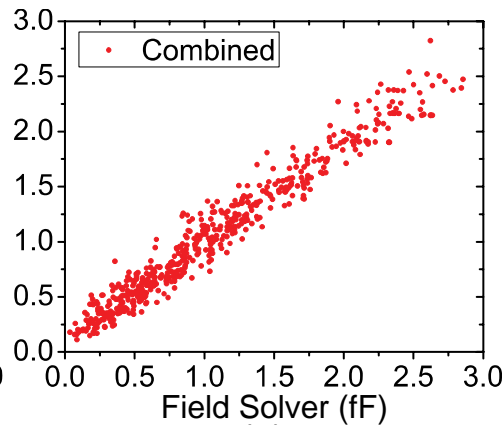
Validation with Full-chip Layout

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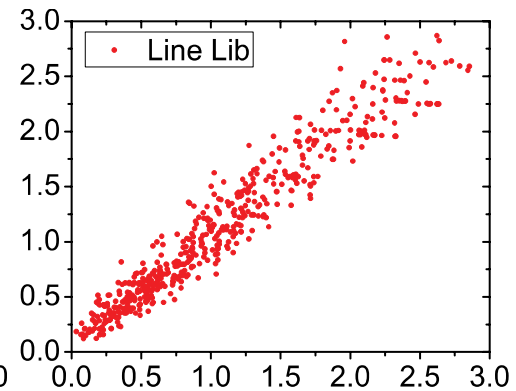
- A 2-die FFT64 design ($380\mu\text{m}\times 380\mu\text{m}$, 330 TSVs) is used for extraction validation, and the results show that combining both line and ring library is fast and highly accurate



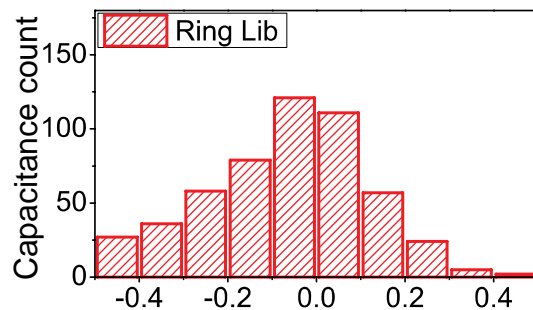
(a)



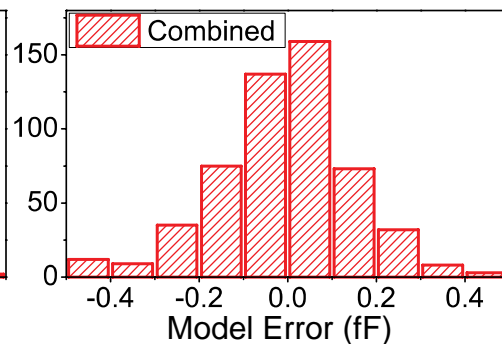
(b)



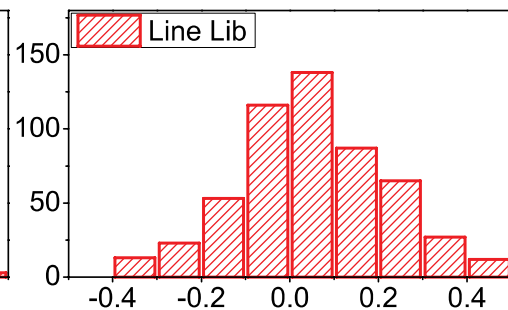
(c)



(d)



(e)



(f)

Validation on **Full-chip** Layout (cont.)

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- **Highly fast and accurate on the full-chip level**
 - **Error is computed against the field solver**

	Field solver	Ring lib	Combined	Line lib
Total cap (fF)	590	538	579	618
Total cap error	-	-8.3%	-1.9%	+5.3%
Correlation coefficient	-	0.971	0.981	0.966
Average error (fF)	-	0.171	0.112	0.163
	Field solver	Line lib	Corner lib	Ring lib
Library generation time	-	8h	9h	18h
Runtime	7.5h	5.8s		
Memory space	>500MB	20MB		

Full-chip TSV-to-wire Impact

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- Multi-TSV models are built for TSV-to-TSV coupling[1]
- STA and statistical power calculation: **Primetime**
- Worst-case total TSV noise calculation: **HSPICE**

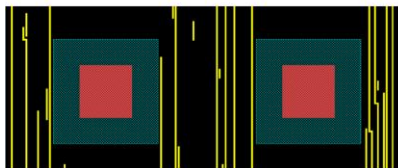
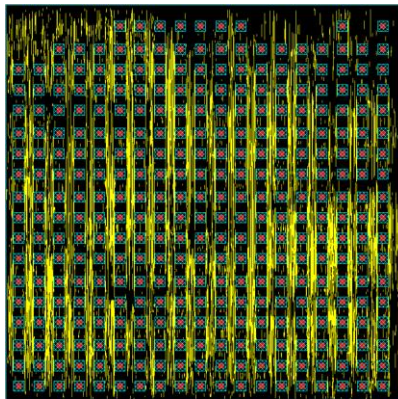
With TSV-to-wire cap?	No	Yes
Total TSV MOS cap (pF)		4.47
Total TSV-to-TSV coupling cap (pF)		0.74
Total TSV-to-wire coupling cap (pF)		2.01
Longest path delay (ns)	4.48	5.08 (+13.4%)
Total TSV net power (mW)	0.303	0.356 (+17.6%)
Total net switching power (mW)	2.42	2.50 (+3.3%)
Total power (mW)	22.9	23.0 (+0.43%)
Total worst-case TSV noise (V)	32.5	78.2 (+104%)

Increasing Routing KOZ

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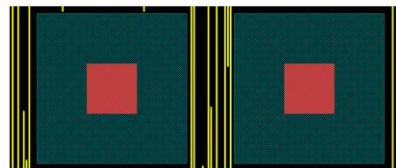
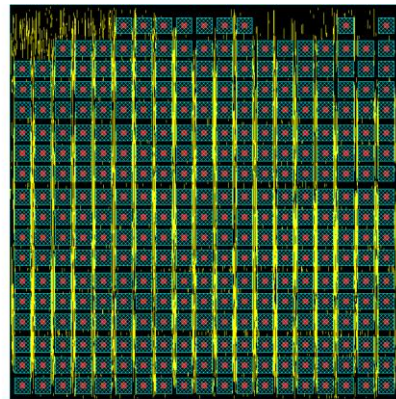
- Increase minimum distance allowed for the nearest wire
 - Decrease the number of coupling wires
 - Increase routing congestion on other layers
 - **No silicon area overhead**

2.5 μ m KOZ

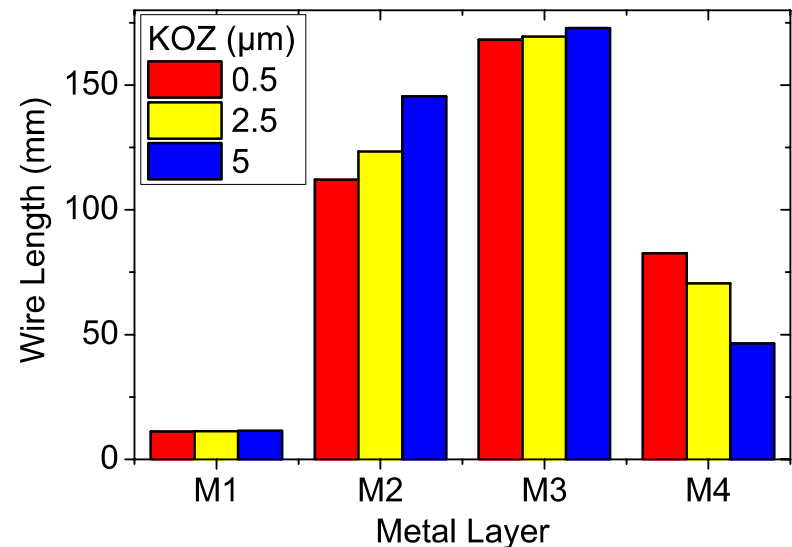


(a)

5 μ m KOZ



(b)

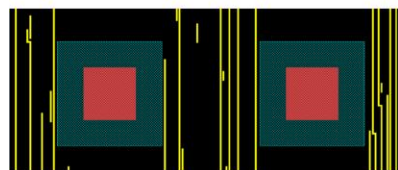
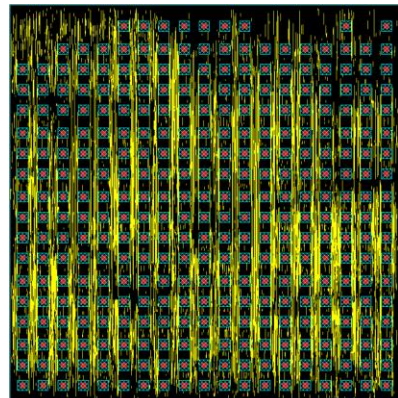


Increasing Routing KOZ (cont.)

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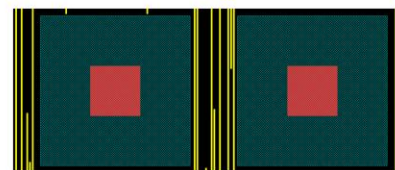
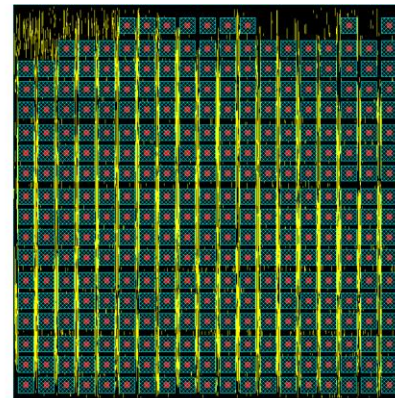
Routing KOZ size (μm)	0	2.5	5
Longest path delay (ns)	5.08	4.95 (-2.6%)	4.77 (-6.1%)
Total TSV net power (mW)	0.356	0.342 (-3.9%)	0.327 (-8.1%)
Total net switching power (mW)	2.50	2.47 (-1.2%)	2.45 (-2.0%)
Total noise on TSV net (V)	78.2	67.0 (-14.3%)	42.9 (-45.1%)

2.5 μm KOZ



(a)

5 μm KOZ

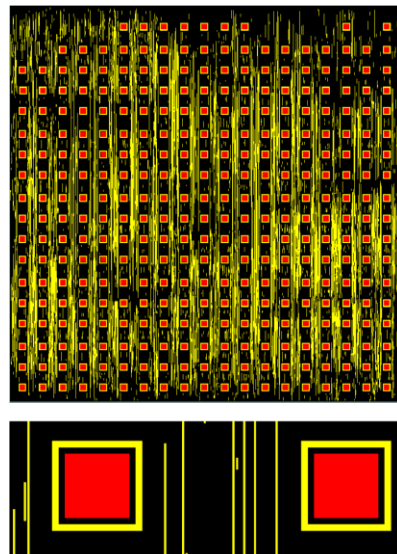


(b)

Guard Ring protection

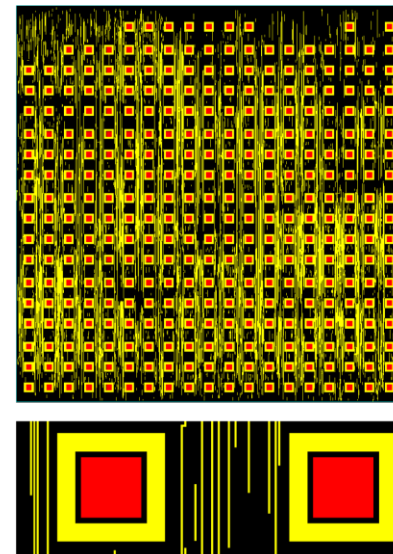
Guard ring width (μm)	0	0.5	1.5
Longest path delay (ns)	4.95	4.98 (+0.6%)	5.01 (+1.2%)
Total TSV net power (mW)	0.342	0.351 (+2.6%)	0.358 (+4.7%)
Total net switching power (mW)	2.47	2.475 (+0.2%)	2.479 (+0.4%)
Total noise on TSV net (V)	67.0	58.0 (-13.4%)	53.6 (-20.0%)

0.5 μm guard ring



(a)

1.5 μm guard ring



(b)

- **This work is a collaboration with Mentor Graphics**
- **The project is extended and planned for further technology transfer and we have regular meeting with Mentor Graphics**
- **This work is first published in DAC14, San Francisco**
- **It is demonstrated to Mentor, Cadence, Synopsys during company visits**
-

- **E-field sharing effects need to be considered for accurate TSV-to-wire extraction**
- **TSV-to-wire coupling has non-negligible impact in full-chip timing, power and TSV noise**
- **Increasing routing KOZ and using wire guard ring can reduce TSV-to-wire coupling effectively**

Thank you!